

	Hits	Search Text	DBs
28	1	430/324.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	1	430/322.ccls. and (((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4 near19 monomer\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	1	430/320.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	0	430/311.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	1	((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4	US-PGPUB
33	1	((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
34	0	430/313.ccls. and (((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4 near19 monomer\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB